

Supplementary Information for:

**Multiferroism in hexagonally stabilized TmFeO₃ thin films
below 120 K**

Suk-Jin Ahn,^{ad} Jung-Hoon Lee,^a Hyun Myung Jang^{ab*} and Young Kyu Jeong^{cd*}

^a Department of Materials Science and Engineering, Division of Advanced Materials Science, Pohang University of Science and Technology (POSTECH), Pohang 790-784, Republic of Korea

^b Department of Physics, Pohang University of Science and Technology (POSTECH), Pohang 790-784, Republic of Korea

^c Department of Materials Science and Engineering, Northwestern University, Evanston, IL 60208, USA

^d Memory Manufacturing Operation Center, Samsung Electronics Co., Ltd., Hwaseongsi 449-711, Republic of Korea

* To whom correspondence should be addressed: Hyun Myung Jang: hmjang@postech.ac.kr and Young Kyu Jeong: young.jeong@northwestern.edu

Methods

Film Fabrication and Characterizations.

An epitaxial Pt (111) film as the bottom-electrode layer was grown on the Al₂O₃ (0001) substrate using RF magnetron sputtering. A pulsed laser deposition method was then used for the fabrication of a 60-nm-thick hexagonal TmFeO₃ (h-TFO) film layer on the Pt(111)/sapphire (Al₂O₃) substrate at a laser energy density of $\sim 1.5 \text{ J/cm}^2$ with the repetition rate of 3 Hz. The substrate temperature was held at 850 °C in an oxygen ambience of 200 mtorr. After the PLD growth, a Pt top-electrode layer was deposited to make a capacitor structure.

The temperature-dependent spontaneous polarization was evaluated by measuring the pyrocurrent using a Keithley 487 picoammeter with a sweeping rate of 2 °C /min. Starting at 100 °C, the film was cooled down under an electric poling field of 800 kV/cm along the *c*-axis before measuring the pyroelectric current on heating. *P-E* hysteresis loops with a virtual ground mode were obtained using a Precision LC system (Radiant Technologies, Inc.). Magnetic properties were examined by measuring M-H (SQUID magnetometer, Quantum Design) and M(T) curves (MPMS).

First Principles Calculations

We performed *ab initio* DFT calculations on the basis of the generalized gradient approximation (GGA) and the GGA + U method implemented with the projector augmented wave (PAW)^{S1,S2} pseudopotential using the Vienna *ab initio* Simulation Package (VASP).^{S3,S4} We adopted (i) a 5×5×3 Monkhorst-Pack *k*-point mesh centered at Γ ,^{S5} (ii) a 500eV plane-wave cutoff energy, and (iii) the tetrahedron method with the Blöchl corrections for the Brillouin zone integrations.^{S6} The Hubbard U_{eff} of 4.5 eV for Fe was chosen on the basis of previous studies.^{S7} We explicitly treated 9 valence electrons for Tm ($5p^65d^16s^2$), 8 for Fe ($3d^64s^2$), and 6 for O ($2s^22p^4$). All structural relaxation was performed with a Gaussian broadening of 0.05 eV.^{S7} The ferroelectric polarization was calculated using the Berry-phase method.^{S8}

Optimized atomic positions in hexagonal TmFeO₃

	P6 ₃ cm			P6 ₃ /mmc		
	x	y	z	x	y	z
Tm1	0	0	0.2766	0	0	0.2500
Tm2	0.3333	0.6667	0.2328	0.3333	0.6667	0.2500
Fe	0.3337	0	0	0.3333	0	0
O1	0.3056	0	0.1664	0.3333	0	0.1667
O2	0.6394	0	0.3370	0.6667	0	0.3333
O3	0	0	0.4770	0	0	0.5000
O4	0.3333	0.6667	0.0209	0.3333	0.6667	0.0000

Table S1. In our density-functional theory (DFT) calculations, the following ground-state lattice parameters at zero pressure were obtained: the hexagonal unit-cell parameters of $a = 6.0057 \text{ \AA}$ and $c = 11.6867 \text{ \AA}$ for $P6_3cm$ phase. Using these parameters, we also computed $P6_3/mmc$ phase.

Computed double-well potential

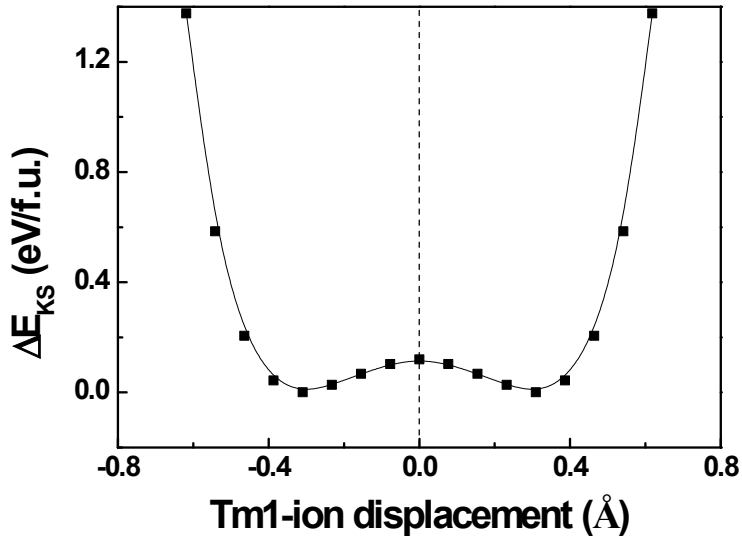


Figure S1. According to the computed double-well potential, the barrier height for the dipole switching along the c axis is 0.1198 eV per unit cell. This clearly demonstrates the thermodynamic stability of the ferroelectric $P6_3cm$ phase over the centrosymmetric $P6_3/mmc$ phase. The total Kohn-Sham (KS) energy calculations indicate that the ferroelectric $P6_3cm$ phase is substantially more stable than these phases. According to our density-functional theory (DFT) calculations, the equilibrium off-center displacement of the Tm ion along the c axis is antiparallel to that of the O_A ion but with the same displacement of 0.290 Å. This indicates that the net off-centering distortion is 0.580 Å.

Local distances between Tm and O ions

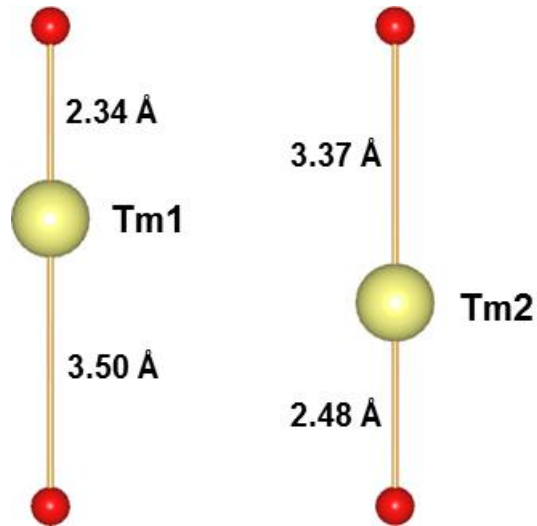


Figure S2. The h-TFO compound possesses two distinct Tm-ion sites in the ferroelectric state. The first dipole (O_A -Tm1- O_A) is antiparallel to the second one (O_A -Tm2- O_A). In addition, the amplitude of the local Tm1 off-centering is larger than that of the local Tm2 off-centering. Thus, the net polarization is parallel to the c axis of $P6_3cm$.

Capacitance – Voltage Curves

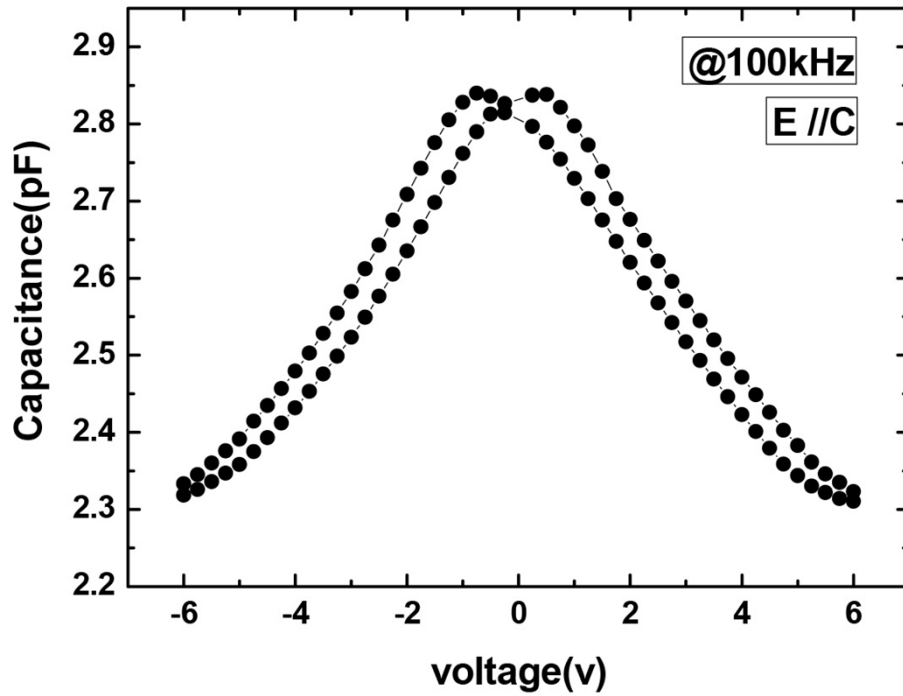


Figure S3. Capacitance-voltage curve of the Pt/h-TFO/Pt capacitor obtained at 100 kHz with the probing electric field parallel to the film-grown direction, [0001]. The ferroelectricity with a non-zero remnant polarization was also confirmed by obtaining a butterfly-shaped hysteresis C-V curve.

Pyroelectric Current Data

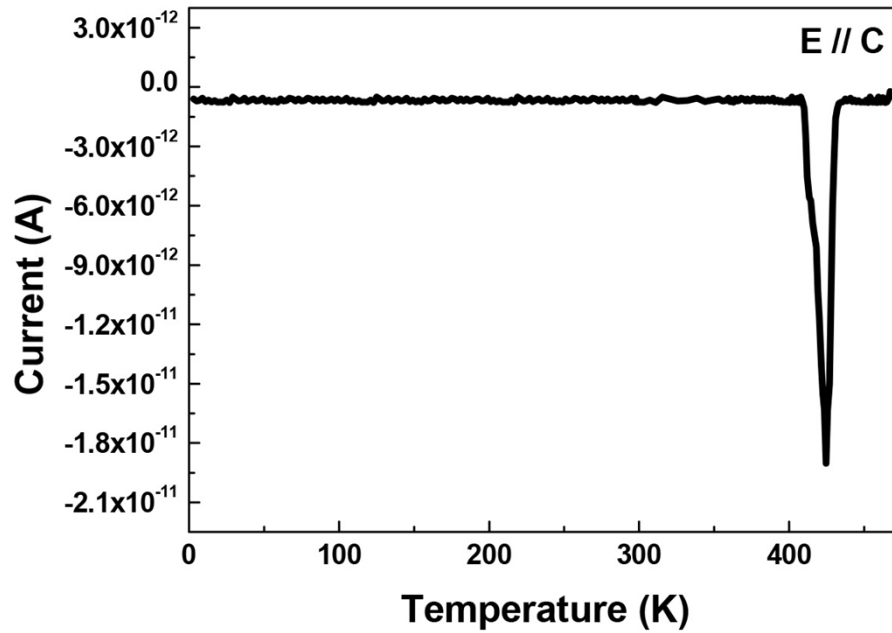


Figure S4. Temperature-dependent pyroelectric current of the h-TFO film obtained using a Keithley 487 picoammeter with a sweeping rate of $2^\circ\text{C}/\text{min}$. The onset of the para-to-ferroelectric transition is observed at ~ 430 K (T_c , Curie temperature), as described in the main manuscript.

Temperature dependent relative dielectric permittivity curves

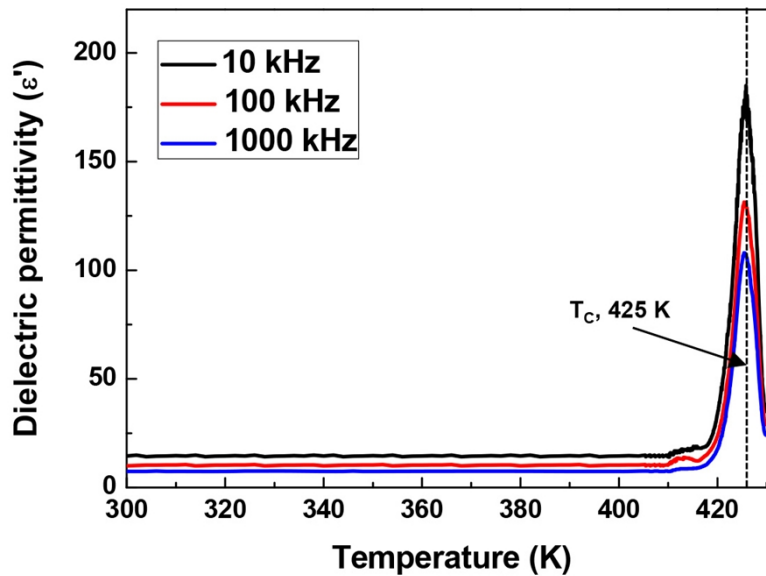


Figure S5. Temperature dependent relative dielectric permittivity curves of the h-TFO film measured at various ac probing frequencies. Note that the peak temperature of the dielectric permittivity coincides well with the onset of the ferroelectric transition at ~ 430 K.

* References

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